#### Amendments to Claims

This listing of claims will replace all prior versions and listing of claims in the application:

#### Listing of Claims

- 1. (previously presented) A detector comprising:
  - a first wafer having a cathode;
  - a second wafer having a chamber, formed on the first wafer;
  - a third wafer, having an anode, formed on the second wafer, and
  - a eutectic bond between at least one of the first and second wafers or between the
- (original) The detector of claim 1, wherein the chamber is sealed from an environment external to the chamber.
- 3. (original) The detector of claim 2, wherein the third wafer is transparent to detectable light.
- 4. (original) The detector of claim 3, wherein the chamber contains a gas.
- 5. (original) The detector of claim 4, wherein the gas is a mixture of H2 and Ne.
- (original) The detector of claim 5, wherein the distance between the anode and cathode is between 25 microns and 75 microns.
- 7. (previously presented) The detector of claim 5, wherein the eutectic bond is between the first and second wafers

- (previously presented) The detector of claim 7, further comprising a eutectic bond between the second and third wafers.
- (original) The detector of claim 8, wherein the first, second and third wafers comprise silica.
- 10. (original) The detector of claim 9, wherein:

the first wafer has a conductor connected to the cathode for a connection external to the detector; and

the third wafer has a conductor connected to the anode for a connection external to the detector

- 11. (original) The detector of claim 10, wherein the anode is a grid.
- 12. (original) The detector of claim 11, wherein:

the anode comprises a conductive metal; and the cathode comprises a conductive metal.

13-19. (canceled)

20. (previously presented) Means for detecting comprising:

means for emitting electrons;

means for collecting electrons; and

means for containing a gas situated between the means for emitting electrons and the means for collecting electrons; and

wherein the means for emitting electrons, the means for collecting electrons and the means for containing a gas are situated within a wafer structure;

wherein the wafer structure comprises silica wafers bonded with a cutectic material

- 21. (original) The means of claim 20, wherein light impinging the gas may cause a current flow between the means for emitting electrons and the means for collecting electrons.
- 22. (original) The means of claim 20, wherein:

the gas comprises neon; and the light is UV.

23. (previously presented) A sensor comprising:

a cathode wafer;

a cavity wafer bonded to the cathode wafer; and

an anode wafer bonded to the cavity wafer; and

#### wherein:

the cavity wafer has a cavity having first and second openings sealed by the cathode wafer and the anode wafer, respectively;

the wafers comprise silica; and

the wafers are bonded with a eutectic material.

- 24. (original) The sensor of claim 23, further comprising:
  - a cathode situated on the cathode wafer proximate to the first opening of the cavity; and
  - an anode situated on the anode wafer proximate to the second opening of the cavity.
- 25. (original) The sensor of claim 24, wherein the cavity has a light-admissible end.

- 26. (original) The sensor of claim 25, wherein the cavity contains a gas.
- 27. (original) The sensor of claim 26, further comprising electrical connections to the cathode and the anode.
- 28. (canceled)
- 29. (previously presented) The sensor of claim 26, wherein the gas comprises neon.
- (original) The sensor of claim 29, wherein: the gas further comprises hydrogen; and the portion of neon in the gas is greater than fifty percent.
- 31. (original) The sensor of claim 24, wherein the cathode wafer, the anode wafer and cavity wafer comprise a plurality of cathodes, anodes and cavities, respectively, that forms a plurality of individual sensors.
- 32. (original) The sensor of claim 31, wherein the bonded cathode wafer, the anode wafer and cavity wafer are cut into individual chips.